SOV/21-59-9-12/25 on the Problem of the Solubility of Boron in Silicon at a temperature of 1,200° C. The data obtained on the solubility at room temperature are close to the resolubility at room temperature are close to the resolubility of Pearson and Bardeen / Ref 6 / but differ to a sults of Pearson and Bardeen / Ref 6 / but differ to a loger also shows the existence of a eutetic correspondpaper also shows the existence of a eutetic corresponding to 18 at. per cent of boron at a melting point of 1,370°C. The course of the solubility diagram at a light content of boron shows the possibility of the igher content of boron shows the possibility of the and silicon which probably can be expressed by the and silicon which probably can be expressed by the formula B<sub>2</sub>Si and which melts congruently at temperaformula B<sub>2</sub>Si and which melts congruently at temperatures close to 1,700 - 1,800°C. This composition was tures close to 1,700 - 1,800°C. This constructed for tained data, a hypothetical form is constructed for tained data, a per cent of boron (see Graph Nr 2).

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On the Problem	n of the Solubility of Boron in Silicon There are 2 graphs and 8 references, 4 of which are Soviet, 3 English and 1 unidentified. Instytut metalokeramiky i spetsial'nykh splaviv AN URSR (Institute of Metal Ceramics and Special Alloys of the AS of UkrSSR)
PRESENTED:	By V.N. Svyechnykov, Member, AS UkrSSR
SUBMITTED:	April 13, 1959
Card 3/3	

•• ••	66299	
15. 2220, AUTHORS:	5.2400(A) Paderno, Yu. B., Serebryakova, T.I. and Samsonov, G.V.	
TITLE: PERIODICAL:	Production and Some Properties of Hainium Boride Merotryve metally, 1959, Nr 11, pp 48-50 (USSR)	
ABSTRACT :	Considerable work has been carried out on titalium and zirconium borides. Little study has been made of hafnium boride, but preliminary investigations show it has even better properties. There is probably only one stable compound - the diboride with AlB <sub>2</sub> type structure. It has been obtained by precipitation from the gas phase (Ref. 2.3). In the present work it was produced by the reduction of hafnium oxide by boron or boron carbide in a vacuum furnace. The relation of the free energy with temperature is -	
	$\Delta F = 358.2 \times 10^3 - 175.05T$ $\Delta F = 91.9 \times 10^3 - 39.1T$	
Card 1/2	for reduction by boron carbide and boron respectively. The reduction with carbide takes place at somewhat higher temperatures than with boron. At a pressure	



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nov, H.V. and Paderno, Yu.B. Fric Properties of Borides of Rare-Earth Metals Vidi Akademiyi nauk Ukrayins'koyi RSR, 1959, Nr 11, 215 - 1218 (USSR) is an account of a study of the possibility of zation of hexaborides of alkaline and rare-earth s as cathodes in electric devices. Furthering
ridi Akademiyi nauk Ukrayins'koyi RSR, 1959, Nr 11, 215 - 1218 (USSR) is an account of a study of the possibility of zation of hexaborides of alkaline and rare-earth s as cathodes in electric devices. Furthering
is an account of a study of the possibility of zation of hexaborides of alkaline and rare-earth s as cathodes in electric devices. Furthering
zation of hexaborides of alkaline and rare-earch s as cathodes in electric devices. Furthering
results of studies of this matter contained in s listed in the reference block, the authors in- gated the electric resistance and the thermo . in hexaborides of lanthanum, cerium, praseo- im, neodymium, samarium and gadolinium. The ex- ments were conducted in described installations, 11 and 12 7, in the region from room tempera- to 700-800°C. Measurements were made on samples owders of respective hexaborides by hot pressing. results are compiled in a table. It was found hexaborides are metallic conductors with hole
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Electric Pro	operties of Bo	orides of Rare-E	SOV/21-	66650 59-11-10/27	
ASSOCIATION: PRESENTED:	conductivity structure, a less than re thermo-emitt recommend co from one ano nic levels a of electrons rides as lan terbium, cer yttrium and s There are 2 t Soviet, 2 Ger Instytut meta stitute of Me AS UkrSSR)	which tallies and that the hex sistance in met ers with high r mbining borides ther in congest nd have lower va , especially suc thanum-cerium, c thanum-cerium, c scandium borides tables and 19 re man and 3 Engli alokeramiky i sp etallogeramics an	well with thei aborides have als. In order esistances, the which greatly on of d- and f alues of work f ch combinations erium-gadolini or a combination with lanthani ferences, 14 o sh. etssplaviv AN d Special Allo	a resistance to obtain a authors differ -electro- unction of bo- um, cerium- on of te borides. f which are	
Card 2/2				4	

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AUTHORS:	Samsonov, G.V., Dzeganovskiy, V.P. and Semashko, I.A.
TITLE:	Europium Hexaboride (Geksaborid evropiya)
PERIODICAL	L: Kristallografiya, 1959, Vol 4, Nr 1, pp 119 - 120 (USSR)
ABSTRACT:	has nither been unexamined. It was synthesized
	by the reaction $Eu_2O_z + 3B_1C = 2EuB_c + 3CO_in$ where
	photographs were taken of the product which contained less than $0.02\%$ C and was dark grey. The unit cell is cubic with a = $4.163 \pm 0.001$ kX and space group OI
	characteristic of all the hexaborides of the rare earths. The X-ray density is $4.99 \pm 0.01$ g/cm <sup>2</sup> . The atomic radii of Eu and Yb are greater than those of the other rare earths and their unit cells are correspondingly greater (mostly about 4.14). The work function of EuB <sub>6</sub> (for an emission exact
Card1/2	(for an emission constant of $A = 1000 - 5000 \text{ A/cm}^2$ ) was found to be 4.90 eV which is higher than that of any other rare-earth hexaboride. It indicates the maximum multiplicity and consequently the greatest binding of the electrons of Eu which has in the normal state 7 electrons

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W: 11 1 ASSOCIATION: AN	n the 4f-shell, wi he 5d-shell; such all in the work fur ith $EuB_6(\phi_{GdB} = 2)$ l references, 9 of English, 1 German Institut metallo	A 5d-electro a 5d-electro action of its 1 2.06 eV). Ther which are Sovi and 1 Scandina keramiki i spe	Dexaboride by ce are 2 figu .et, 1 intern. .vian.	trons in uses a sharp comparison res and ational,
Sourrand:	loys of the Ac.Sc. August 22, 1958	, Ukrainian SS	R)	cial:
Card 2/2				

sov/70-4-4-11/34 Samsonoy, G.V., Zhuravlev, N.N., Paderno, Yu.B. and The Synthesis and Properties of Samarium Hexaboride Melik-Adamyan, V.R. AUTHORS: Kristallografiya, 1959, Vol 4, Nr 4, pp 538-541 (USSR)  $SmB_6$  was prepared by  $Sm_2^0_3 + 3B_4^2C = 2SmB_6 + 3C0$ , the TITLE:  $Sm_2^{0}$  + 3B<sub>4</sub>C being previously heated as powders to PERIODICAL:  $\sim$  350 °C and pressed into pellets which were heated  $\sim$  350 °C and pressed into pellets which were heated in vacuo for 1 hour at 1 000 and then 10-15 min at 1 600 °C. An alternative method,  $Sm_2O_3 + 15B =$ ABSTRACT: =  $2SmB_6$  + 3B0 , was also successful. Heating for 1 hour at 1 650 °C gave SmB<sub>6</sub> in a finergrained form than did the  $B_4C$  method. SmB<sub>6</sub> is dark blue. It was examined in an RKU-114 powder camera and proved to be cubic, with the CaB<sub>6</sub> structure and cell Observed and calculated intensities were compared. size  $a = 4.128 \pm 0.003$  Å. Card1/3

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 $\frac{\text{SOV}/70-4-4-11/34}{\text{d}_{\text{calc}}}$ The Synthesis and Properties of Samarium Hexaboride  $d_{\text{calc}} = 4.85 \text{ g/cm}^3.$ The coefficient of emissivity  $\epsilon_{\lambda}$   $d_{\text{calc}} = 4.85 \text{ g/cm}^3.$ The coefficient of emissivity  $\epsilon_{\lambda}$   $d_{\text{calc}} = 0.85 \text{ g/cm}^3.$ The coefficient of emissivity  $\epsilon_{\lambda}$   $\log \epsilon_{\lambda} = c/\lambda (1/T - 1/T_{\lambda}),$ where c is the emissivity of an absolutely black body, and  $\lambda = 650 \text{ mµ}, \text{ decreasing linearly from 0.75 at}$   $4.79 \text{ g/cm}^3.$ The microhardness was 2 500  $\pm$  300 kg/mm<sup>2</sup>.  $4.79 \text{ g/cm}^3.$ The microhardness was 2 500  $\pm$  300 kg/mm<sup>2</sup>. The electrical resistance was  $\sim 388 \ \mu\Omega \cdot \text{cm}$ . The thermo  $e.m.f. \text{ was measured between 20 and 700 °C.$ The melting 20 and 60 °C it was found to be 3.4  $\mu$ V/°C. The melting 20 and 60 °C. The coefficient of thermal expansion from 20 to 800 °C was  $6.5 \times 10^{-6}.$ The work function was 4.4 eV. These physical

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CIA-RDP86-00513R001447020001-2

Sov/70-4-4-1/34 The Synthesis and Properties of Samarium Hexaboride properties are compared with those of the rare earth hexaborides. There are 3 figures, 1 table and 7 references, of which 5 are Soviet, 1 German and 1 English. ASSOCIATIONS: Otdel tugoplavkikh soyedineniy Institute metallokeramiki i spetsial'nykh splavov AN UkrSSR (Section of Refractory Compounds, Institute of Metallo-ceramics and Special Alloys of the Ac.Sc., Ukrainian SSR (Department of Solid-state Physics of Moscow State University imeni M.V. Lomonosov) SUBMITTED: January 7, 1959 Card 3/3

APPROVED FOR RELEASE: 08/22/2000

# CIA-RDP86-00513R001447020001-2

sov/70-4-4-12/34 Samsonov, G.V., Paderno, Yu.B. and Serebryakova, T.I. On the Borides of Praesodymium, Erbium and Terbium AUTHORS: Kristallografiya, 1959, Vol 4, Nr 4, pp 542-544 (USSR TITLE: The borides of Pr, Er and Tb were made from the oxides PERIODICAL: ABSTRACT: by the reactions:  $Me_2O_3 + 3B_4C = 2MeB_6 + 3CO$  $Me_2O_3 + 15B = 2MeB_6 + 3BO$ and which were carried out in an electric resistance furnace under vacuum at 1 500 - 2 000 °C. X-ray powder photographs were taken in a 57.3 mm camera. with a = 4.12 Å. With Er a product identical with UB<sub>4</sub> was found,  $presumably ErB_4$  with a tetragonal cell with a = 7.08, c = 4.02 Å. On the cooler parts of the furnace a blue film of ErB6 was condensed and has been described earlier (V.S. Neshpor and the author - Ref 8). Card1/2

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On the Bori	ides of Praesodymium, Erbium and Terbium	
	For Tb, a mixture was obtained: cubic TbB <sub>6</sub> with $a = 4.11$ Å and tetragonal TbB <sub>6</sub> with $a = 7.13$ and	
	c = 4.07 A. Intensities were calculated to index the pattern unambiguously. The may have two electronic	
	configurations, $4f^85d^16s^2$ or $4f^96s^2$ and a choice should be possible on the basis of physical properties. Measurements of the work function for TbB <sub>6</sub> gave (for an	
	emission current of 120 $A/cm^2 deg^2$ ) $\varphi = 3.1 eV$ , which corresponds to $4f^5 5d^4 6s^2$ and gives a decisive choice. Powder data for the four compounds are tabulated. There are 4 tables and 12 references, of which 6 are Soviet, 2 German, 2 English and 2 French.	
ASSOCIATIO	N: Institut metallokeramiki i spetsial'nykh splavov AN UkrSSR (Institute of Metallo-ceramics and Special Alloys of the Ac.Sc.Ukrainian SSR)	
SUBMITTED:	December 6, 1958	
Card2/2		
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5.2100	77293 S0V/63-4-6-27/37
AUTHORS:	Samsonov, G. V., Obolonchik, V. A., Kulichkina, G. N.
TITLE:	Brief Communications. The Fusion Diagram of ${\rm KBF}_4\cdot{\rm KC1}$ System
PERIODICAL:	Khimicheskaya nuaka i promyshlennost', 1959, Vol 4, Nr 6, pp 804-805 (USSR)
ABSTRACT:	The method of obtaining boron by electrolysis of melts has been least investigated, but it might have industrial value if sufficiently developed technologi- cally. For the electrolysis, a bath containing $B_2O_3$ , MgO, and MgF <sub>2</sub> was used, and 92% pure boron was obtained at 110 <sup>0</sup> . In the present work, the fusion curve of system KBF <sub>H</sub> -KCl was investigated. Starting
	materials were KCl, and $\text{KBF}_4$ obtained from borofluoric
Card 1/3	acid. The thermal analysis was carried out with a Kurnakov pyrometer. Melting was done in platinum

CIA-RDP86-00513R001447020001-2

77293 Brief Communications. The Fusion Diagram SOV/63-4-6-27/37 of KBF<sub>h</sub>.KCl System crucibles. From the results of thermal and chemical analyses (determination of boric acid), a fusion curve of the above system was prepared. A chemical compound having the formula KCl·llKBF (mp 590° ) was detected in the system. The above compound forms a eutectic mixture with  ${\rm KBF}_4$  , containing 97.8% of .  $KBF_{li}$  (mp 508°). The second eutectic system (mp 471°) contains 87.6% of  ${\rm KBF}_4$  and is formed from KCl·llKBF $_4$ and KCl. There is 1 figure; 1'table; and 7 references, 4 Soviet, 2 French, 1 U.S. The U.S. reference is: U.S. Patent Nr 2572249, 1949. ASSOCIATION: Institute of Cermets and Special Alloys, Academy of Sciences, UkrSSR (Institut metallokeramiki i spetsial'nykh splavov Akademii nauk USSR) SUBMITTED: May 29, 1959 Card 2/3

APPROVED FOR RELEASE: 08/22/2000



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5(2) AUTHORS:	Neshpor, V. S., Samsonov, G. V.
TITLE:	On the Problem of the Electronic Structure and the Condition for the Formation of Borides of the Type MeB <sub>6</sub>
PERIODICAL:	Zhurnal neorganicheskoy khimii, 1959, Vol 4, Nr 9, pp 1967-1969 (USSR)
ABSTRACT:	The electrons necessary for the formation of the 5 covalent bonds in the hexaborides cannot be supplied by boron alone, two of them must be supplied by the metal (Refs 5, 6). The formation of the hexaborides probably depends on the first and second ionization potentials of the metal. The values of the potentials determine the attractive force of the two valence electrons. In table 1 the ionization potentials of the metallic elements of the periodic system are listed. It is concluded that all the metals having first ionization potentials below $6.6 - 6.8$ ev, and second ionization poten- tials below $11.5 - 12$ ev are able to form hexaborides. In reference 8 it was proved that the bivalent metal in the

## CIA-RDP86-00513R001447020001-2

sov/78-4-9-5/44 On the Problem of the Electronic Structure and the Condition for the Formation of Borides of the Type MeB<sub>K</sub> hexaboride may partially be substituted by sodium. The highest electron concentration at which this substitution still takes place, is 1.6 electrons per metal atom. Thus, it follows that the bond of the borine in MeB6 requires 1.6 electrons, the remaining 0.4 electrons per metal atom probably being present as common electrons which would explain the comparatively high electrical conductivity of the hexaborides of bivalent metals. There are 1 table and 15 references, 10 of which are Soviet. ASSOCIATION: Institut metallokeramiki i spetsial'nykh splavov Akademii (Institute for Metal Ceramics and Special Alloys of the nauk USSR Academy of Sciences, UkrSSR) Card 2/1

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### CIA-RDP86-00513R001447020001-2

SOV/78-4-12-16/35 Samsonov, G. V., Koval'chenko, M. S., Production of Disilicides of Difficultly Fusible Metals 5 (2) Verkhoglyadova, T. S. AUTHORS: Zhurnal neorganicheskoy khimii, 1959, Vol 4, Mr 12, TITLE: Pure, finely powdered Ti, Zr, V, Nb, Ta, Cr, Mo, and W were pp 2759 - 2765 (USSR) mixed with silicon powder in stoichiometric ratio, pressed into PERIODICAL: small briquets and annealed in argon atmosphere at 600-1,2000 for 0.5-32 hours. The heating took place in an apparatus de-ABSTRACT: picted in figure 1. The reaction products were analytically tested (under the supervision of T. Ya. Kosolapova) and radio graphically (RKE and KROS cameras) for free and bound Si. The graphically (not and not cameras) for the production of completely homogeneous disilicides is given in table 1. There is an exponential relation between reaction temperature and reaction time (Fig 3), which allowed to calculate the activation energy for the diffusion of Si into the metals. The values of this energy are like wise listed in table 1 and compared with the data given in reference 6 for the activation energy during Si diffusion into compact metal. The fact that the activation energy of metallic Card 1/3

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Production of Disilicides of Difficultly Fusible Metals SOV/78-4-12-16/35 powder is much higher is explained by the crystallization pressure occurring in the formation of disilicide particles which interrupts the contact between metallic and Si particles not yet entered into reaction and complicates diffusion (Refs 7,8). The effect of diffusion-inhibiting oxide films is also likely to be more strongly pronounced in the case of pulverulent mixtures. As a variant, the authors investigated formation of disilicides by vacuum reduction of the metallic oxides according to the formula  $Me_x^0$  + zSi =  $Me_x^{Si}_{z-y}$  + ySi0 and checked the beginning of the reaction by measuring the pressure which rose as a result of SiO formation. The results obtained for Ti, V, Nb, and Ta are listed in table 3. This method requires a more complicated apparatus and is more difficult to employ in industry than the direct fusion of metal with silicon. Furthermore, it yields less pure products and is inappropriate for metals with volatile oxides (Mo,W). The optimum conditions for a direct reaction between metal and silicon are: TiSi2 1000 C, 2 hours; ZrSi2 1000 C, 2 hours; VSi<sub>2</sub> 1200 C, 0.5 hours; NbSi<sub>2</sub> 1000 C, 0.5 hours; TaSi2 < 1100 C < hours; CrSi2, MoSi2 and WSi2 1000 C, 0.5 hours. Card 2/3

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CIA-RDP86-00513R001447020001-2

Production of Disilicides of Difficultly Fusible Metals SOV/78-4-12-16/35 L. M. Khrenova, G. N. Makarenko, and V. P. Dseganovskiy assisted in the experiments. There are 4 figures, 3 tables, and 11 references, 6 of which are Soviet. Institut metallokeramiki i spetssplavov Akademii nauk USSR (Institute of Cermets ASSOCIATION: Academy of Sciences, UkrSSR) July 2, 1958 SUBMITTED: Card 3/3

APPROVED FOR RELEASE: 08/22/2000

CIA-RDP86-00513R001447020001-2

67656 501/126-8-4-19/22 Samsonov, G.V., Neshpor, V.S. and Khrenova, L.M. Hardness and Brittleness of Metalloid Compounds 15. 2220 PERIODICAL: Fizika<sup>w</sup> metallov i metallovedeniye, 1959, Vol 8, Nr 4, 18:6100 ABSTRACT: Specimens of Ti, Zr, Cb, Ta, Cr, Mo, W, JE, JCo and Ni ABSTRACT: Specimens of Ti, Zr, Cb, Ta, Cr, Mo, W, JFe, JCo and Ni silicides and Ti, Zr, Cb, Ta, Cr, Mo, W, JFe, JCo and Ni silicides, of limiting phase composition, were made by sintering nowders of these compounds by hot pressing AUTHORS: sintering powders Wof these compounds by hot pressing with subsequent long annealing at a high temperature made order to remove internal stresses. Microsections made from these specimens were etched in order to expose the grain boundaries and to remove the surface layer which The microhardness grain boundaries and to remove and ing. The microhardnes had been cold worked during grinding. Loads of 20-200 g The experiments have shown that the microwas tested with a PMT-3 instrument. hardness numbers depend on the load used, and this relationship is beyond the limits of accuracy of the measurements the relationship between mismonant The relationship between microhardness number and load was first established by Bochvar et al (Pof h) for relatively coff meterials (Cr. 7n and Amor (Ref 4) for relatively soft materials (Gu, Zn and Armco In other papers (Refs 5-7) the relationship Card iron). 1/4

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CIA-RDP86-00513R001447020001-2

67696 sov/126-8-4-19/22 Hardness and Brittleness of Metalloid Compounds estimating the number and nature of cracks and other defects thereby arising. In order to lower the subjectiveness of this estimation a so-called average brittleness mark is introduced, which is calculated according to the degree of destruction shown by the impression. The estimation of the degree of destruction is carried out according to a 5-mark scale (see Fig 5 and Table 1). Figs 6 and 7 show the dependence of the summary mark of destruction of Table 2 borides and silicides, respectively, on load. shows the brittleness characteristics of metalloid The microhardness number depends on the load at which the investigation is carried out. nature of the relationship between microhardness number compounds. and load of materials with very great and comparatively low hardness is identical and appears to be due to the nature of plastic deformation of the surface of hard characteristics of metalloid compounds obtained by the bodies in microhardness testing. microbrittleness methods in this work agree satisfactoril Card 3/4

CIA-RDP86-00513R001447020001-2



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•	SOV/74-28-2-4/5
5(?) AUTHOR:	Samsonov, G. V., (Kiyev) Borides of Rare Earth Metals (Boridy redkozemel'nykh
TITLE:	Borides of Rare Earth Model metallov)
PERIODICAL:	metallov) Uspekhi khimii, 1959, Vol 28, Nr 2, pp 189-217 (USSR) Borides of rare earth metals have been used in numerous Borides of rare earth metals have been used in numerous, I fields, above all in the field of electronics,
ABSTRACT:	technical lields, At present the methods investigated by
	as well as thereign scientists. Due to the made in the present
	available matericture of borides was the first time as well as
	Stackelberg and 1932 (Ref 2). Hexaborides of use and hy Allard in 1932 (Ref 2). Hexaborides of use and the second mium, gadolinium, erbium and
	ytterblum wells a cubic lattice of boron atoms
Card 1/5	(Fig 1). In one of the first public public earth and rate due of (Fig 1). In one of the first public earth and rate due of the crystallochemistry of borides of alkaline-earth and rate due of the crystallochemistry of borides of alkaline earth and rate due of the crystallochemistry of borides of alkaline earth and rate due of the crystallochemistry of borides of alkaline earth and rate due of the crystallochemistry of borides of alkaline earth and rate due of the crystallochemistry of borides of alkaline earth and rate due of the crystallochemistry of borides of alkaline earth and rate due of the crystallochemistry of borides of alkaline earth and rate due of the crystallochemistry of borides of alkaline earth and rate due of the crystallochemistry of borides of alkaline earth and rate due of the crystallochemistry of borides of alkaline earth and rate due of the crystallochemistry of borides of alkaline earth and rate due of the crystallochemistry of borides of alkaline earth and rate due of the crystallochemistry of borides of alkaline earth and rate due of the crystallochemistry of borides of alkaline earth and rate due of the crystallochemistry of borides of alkaline earth and crystallochemistry of alkaline earth and
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sov/74-28-2-4/5

Borides of Rare Earth Metals of elements of the II., III., and IV. group of the periodic system are formed. All these hexaborides, with the exception of Be- and Mg-compounds, have a cubic structure of the type CaB6. It was found that in the series of cubic hexaborides there are several sub-groups the place of which is determined by the valence of the metal atom. In the formation of hexaborides the metal atom emits 2 external electrons to boron in order to form 5 hybrids connected orbits, which are formed by s, p, and excited d functions. In so far as the hexaborides do not produce any properties of ion compounds, the emission of electrons to boron takes place as a statistic electron exchange between metal and boron atoms. The analysis of experimental material indicates (Ref 12) that hexaborides are actually formed by those metals only the first ionization potential of which does not exceed 6.6.6.8 ev and the second ionization potential not 11.5-12 ev. The following conditions have to be maintained for the formation of metallic hexaborides: 1) a certain value of the first and second ionization potential which does not exceed the critical values; 2) the presence of bivalent electrons on the ns-level; 3) the Card 2/5

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# 50V/74-28-2-4/5

Borides of Rare Earth Metals

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possibility of a participation of the partly filled or empty (n-1)d-level in the bond metal boron. The existence of 5f-levels is not obligatory, however, they play their part in the formation of hexaborides (Ref 5). In this connection all rare earth metals would have to form hexaborides. This is actually the case. For the present only the prometheum and thulium hexaboride are still unknown. In the earliest publications the metallic conductivity of hexaborides was already determined (Ref 1) and confirmed later on (Refs 1, 4, 5, 20, 21, 22). An exact phenomenological analysis of the variation of the electric resistance of hexaborides of rare earth metals is, at present, complicated since there is a lack of data on the resistance of both hexaborides and metals. All hexaborides of rare earth metals are marked by a poor work function of electrons and some of them by high emission fluxes. Their magnetic properties were investigated on samples obtained from media melted by means of electrolysis (Refs 4, 30) (Table 4). The investigation of the susceptibility course with temperature (Fig 9) has shown an approximate linearity of the susceptibility coefficients at high temperatures and a great deviation of the straight

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### CIA-RDP86-00513R001447020001-2

SOV/74-28-2-4/5

Borides of Rare Earth Metals

lines in the temperature range of 0-350°. This is explained by the presence of ferromagnetic impurities in the preparations. The data on the thermo-electromotive force of hexaborides are given in Table 2 . Like borides of transition metals of IV., V., and VI. group of the periodic system borides of So, Y and lanthanides are distinguished by high melting temperatures, hardness, moderate thermal expansion coefficients and chemical stability. There are only few data available concerning chemical properties of hexaborides (Refs 28, 37, 42). Borides of rare earth metals can be obtained by different ways: 1) by direct binding of metal with boron; 2) by electrolysis of molten media; 3) by the reduction of mixtures of metallic oxides and boris anhydrides with carbon; 4) by the reaction taking place between metallic oxides and boron carbide or boron mixture and carbon; 5) by the reduction of metallic oxides with boron. The powders of borides are viscous, brittle and not plastic. By the usual way of sintering of pressed briquettes no compact products can be obtained from them (Ref 51). Several conditions for sintering are given in Table 7 . Compact products can be obtained from borides by casting (Ref 33). In this case, however, a contamination and

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SOV/74-28-2-4/5 Borides of Rare Earth Metals coarsening of the structure must be taken into account. In conclusion it may be stated that the properties and production methods of borides of rare earth metals are not yet sufficiently investigated. There are 11 figures, 7 tables, and 72 references, 47 of which are Soviet. Card 5/5

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SAMSONOY, G.Y. [Samsonov, H.V.], doktor tekhn. nauk; RADOMYSEL'SKIY, I.D. [Radomysel's'kyi, I.D.], kand. tekhn. nauk
Conference on problems of powder metallurgy. Visnyk AN URSE 30 no.3:71-72 Mr '59. (MIRA 12:6)

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## CIA-RDP86-00513R001447020001-2

sov/20-125-2-20/64 Paderno, Yu. B., Serebryakova, T. I. 21(1)AUTHORS: Samsonov, G. V. The Compounds of Terbium With Boron and the Electron Configuration of the Atom of Terbium (Soyedineniya terbiya s borom i elektronnaya konfiguratsiya atoma TITLE: Doklady Akademii nauk SSSR, 1959, Vol 125, Nr 2, terbiya) PERIODICAL: pp 317-318 (USSR) Hitherto, the compounds of nearly all rare-earth metals with boron, with the exception of promethium, terbium, and thulium, are known and have been sufficiently well investigated. ABSTRACT: Among them, the compounds of terbium with boron are of special interest because of the 2 possible variants of the electron structure of the terbium atom (which are described by the configurations  $4f^85d^16s^2$  or  $4f^96s^2$ ). The terbium- and boron compounds were produced by the reduction of terbium oxide by boron carbide  $Tb_2O_3 + 3B_4C = 2 TbB_6 + 3 CO and by boron$  $Tb_2O_3+15B = 2TbB_6 + 3BO$  in accordance with previously Card 1/3

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### CIA-RDP86-00513R001447020001-2

The Compounds of Terbium With Boron and the Electron SOV/20-125-2-20/64 Configuration of the Atom of Terbium described methods (Refs 3, 4). In both cases the reduction took 1 hour at 1650°. The reduction with boron resulted in a blue-colored product, and its X-ray picture is characteristic of the hexaborides of the rare-earth metals with cubic of the neratorization of the structural type  $0_h^1$ . According to the results obtained by calculating the intensities of X-ray reflections, this product was found to be terbium-hexaboride with the lattice period a = 4.11 Å. Reduction of the terbium oxide by boron carbide gave a greyish-brown product, viz. TbB<sub>4</sub> with the identity periods a = 7.13 Å and c = 4.07 Å of the tetragonal lattice. The work function of the electrons in the thermoemission from  $\text{TbB}_6$  is  $\varphi = 3.1$  ev and was determined by V. A. Trigubenko and B. M. Tsarev. This value corresponds to the dependence of the work function of the borides on the ordinal number of the rare-earth metals, which had been determined previously (Ref 2) assuming the electron structure Card 2/3

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The Compounds Configuration	of Terbium With Boron and the Electron SOV/20-125-2-20/64 of the Atom of Terbium	
	$4f^{8}5d^{1}6s^{2}$ of terbium. Thus, of the initially mentioned two structures, the last-mentioned is uniquely confirmed. The existence of the fsd - electron configuration indicates a considerable degree of binding of the electrons of terbium and boron in the sd-band of the hexaboride lattice. The existence of the borides TbB <sub>4</sub> and TbB <sub>6</sub> and their crystallo-chemical characteristics were for the first time the authors. There are 2 tables and 6	
	determined by the authors, by	
ASSOCIATION:	Institut metallokeramiki i spetsial'nykh splavov Akademii nauk USSR (Institute of Metal Ceramics and Special Alloys of the Academy of Sciences, UkrSSR)	
PRESENTED:	December 9, 1958 by S. A. Vekshinskiy, Academician	
SUBMITTED:	December 8, 1958	
Card 3/3		
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	5(2) AUTHORS:	SOV/20-125-4-37/74 Portnoy, K. I., Samsonov, G. V., Solonnikova, L. A. On the Interaction of Boron Carbide With Silicon (K voprosu On the Interactivit karbida bora s kremniyem)
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	TITLE:	On the Interaction of Boron Carbids and o vzaimodeystvii karbida bora s kremniyem)
	PERIODICAL:	Doklady Akademii nauk SSSR, 1959, Vol 129, ML 4, 12 (USSR)
	ABSTRACT:	(USSR) The system boron-silicon-carbon is interesting because of its considerable hardness, its chemical stability and its semi- conductor-properties. In the system boron-carbon e.g. the com- conductor-properties. In the system boron-carbon kg/mm <sup>2</sup> , Refs 1, 2)
		pounds B4C and B6.5 (hardness 5000-5900 ls, pounds B4C and B6.5
		are found, in the 3350 kg/mm <sup>2</sup> (Ref. 5); the properties (Ref. 4).
		After a survey of financia They pressed in a minutes.
en a		and boron calletion part of the silloon version pycnometrically de-
	. 1	In this connection part weight was pychometrics in the specific weight was pychometrics in the specific weight of Si. Figure 1 shows termined, i.e. at 25-30 % by weight of Si. Figure 1 shows termined, i.e. at 25-30 % by weight of the alloys investigated. Already the microstructures typical of the alloys investigated.
	Card 1/3	

On the Interaction of Boron Carbide With Silicon SOV/20-125-4-37/74

at an addition of 2% Si to boron carbide a lighter colored phase forms (Fig 1b). The amount of this phase varies only hittle up to a 20% Si-content, whereas in the case of 28% Si it increases considerably (Fig 1 $\stackrel{1}{\stackrel{1}{\rightarrow}}$ ). In the latter casethe micro-hardness attains 2000 kg/mm<sup>2</sup>. It remains practically constant in the case of further Si-increase (Fig 2a). This phase is apparently a saturated solid solution of boron and carbon (or boron carbide) in silicon. In the case of 25% Si the microstructure shows clear separations of the chemical compound (Fig 1g). The hardness of the second phase increases with increasing silicon-content in the alloy and attains a maximum of  $\sim$  7000  $\rm kg/mm^2$  in the case of an Si-content of 40-50% by weight. It then decreases to 3500-4000 kg/mm<sup>2</sup> (Fig 2b). From 50% silicon onwards a fine-grained eutectic becomes visible between the grains of the silicon- and carbide phase (up to 80% Si-content in the alloy). On an addition of 20% Si to boron carbide the X-ray investigation shows the appearing lines of a new phase. They are most clear at 35-40% Si; at 50-70% Si they pass over into the lines of the solid solution of boron and carbon in silicon, which are well marked at 75% Si (Fig 3). The maximum of electric resistance of the samples is attained at 28-35% Si in the alloys. From the above it is

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	possible to draw a conclusion on the formation of a ternary phase of boron with silicon and carbon which may have the composition $B_5SiC_2$ . Its hardness of ~7000 kg/mm <sup>2</sup> explains its
	high grinding capacity (Ref 9). This phase has a constant resistivity to oxidation in air, at least up to 1200, to mineral acids and their mixtures also in the case of boiling. There are 3 figures and 9 references, 5 of which are Soviet.
ASSOCIATION: PRESENTED:	Vsesoyuznyy institut aviatsionnykh materialov (All-Union Institute of Aviation Material). Institut metallokeramiki i spetssplavov Akademii nauk SSSR (Institute of Powder Metal- lurgy and Special Alloys of the Academy of Sciences USSR) December 16, 1958, by A. A. Bochvar, Academician
SUBMITTED:	December 16, 1958

# CIA-RDP86-00513R001447020001-2



CIA-RDP86-00513R001447020001-2

6.V. SAMSONOV SOV/4874 PHASE I BOOK EXPLOITATION Rakovskiy, Valentin Sergeyevich, Grigoriy Valentinovich Samsonov, and Iosif Ivanovich Ol'khov Osnovy proizvodstva tverdykh splavov (Fundamentals of Carbide-Alloy Production) Moscow, Metallurgizdat, 1960. 232 p. Errata slip inserted. 5,200 copies printed. Ed.: A. K. Natanson; Ed. of Publishing House: M. S. Arkhangel'skaya; Tech. Ed.: P. G. Islent'yeva. PURPOSE: This textbook is intended for students of nonferrous metallurgy tekhnikums, and engineers and technicians in the hard-alloy industry. COVERAGE: The handbook was written in accordance with the course entitled "The Production of Hard Alloys," taught at tekhnikums specializing in nonferrous metals. It contains the fundamentals of powder metallurgy, manufacturing processes of all types of carbide alloys, characteristics of their properties, and inspection methods. The last section is devoted to the fundamentals of degree design projects. This book is Card 1/9

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50V/5227 Samsonov, Grigoriy Valentinovich [ Professor, Doctor of Technical Sciences], Lev Yakov-levich Markovskiy [Candidate of Chemical Sciences], Aleksey Fomich Zhigach[Doc-tor of Chemical Sciences] and Mikhail Georgivevich Valveshko tor of Chemical Sciences], and Mikhail Georgiyevich Valyashko Bor, yego soyedineniya i splavy (Boron, Its Compounds and Alloys) Kiyev, Izd-vo AN UkrSSR, 1960. 589 p. 3,000 copies printed. Sponsoring Agency: Akademiya nauk Ukrainskoy SSR. Institut metallokeramiki i Ed. (Title page): G. V. Samsonov, Professor, Doctor of Technical Sciences; Resp. Ed.: I. N. Frantsevich, Corresponding Member of the Academy of Sciences Harfill: Rd. of Dublishing House: 7. 8. Pokrovskava: Tech. Ed.: V. Ye-UkrS.R; Ed. of Publishing House: Z. S. Pokrovskaya; Tech. Ed.: V. Ye. PURPOSE: This book is intended for scientific workers and engineers in the metallurgical, machine building, chemical, and electronic industries. It may also be used by advanced students. Card-1/12>-

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<ul> <li>Ya. S. Umanskiy are cited along the Scientific Council of the insolvent Union. The authors thank the Scientific Council of Metal Ceramin metallokeramiki i spetsial 'nykh splavov (Institute of Metal Ceramin Special Alloys), Academy of Sciences, Ukrainskaya SSR. They also special Alloys), Academy of Sciences, Ukrainskaya SSR. They also essor Yu. V. Morachevskiy. Most of the chapters are accompanied be the companies of the chapters are accompanies.</li> <li>TAHLE OF CONTENTS: Introduction</li> <li>Ch. I. Geochemistry of Boron (M. G. Valyashko)</li> </ul>	on stock entary boron, es, pro- ys with d and ap- in elec- emistry v, and in the citut es and thank Prof-	
The Geochemistry of Boron (M. G. Valyashko)	3	
Ch. I. Geochemicory Ch. II. Boron Stock and Its Processing (M. G. Valyashko) Card-2/12	7 25	

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AUTHOR :

TITLE:

Samsonov, G.V. and Neshpor, V.S. Alloys of rare metals with bor and silicon for some purposes of electrical and radioengineering Referativnyy zhurnal. Avtomatika i radioelektronika, no. 4, 1961, 3, abstract 4 Gl5 (V sb. Redk. metally i splavy, M., Metallurgizdat, 1960, 392-417) PERIODICAL:

The conditions of obtaining silicides and borides of rare metals are investigated and their physical properties are studied for possible application. The silicides are obtained by heating the mixture of the components in powdered form at a pressure of 250 kg/cm<sup>2</sup> and at a temperature of 1300-2150 °C. The synthesis of the borides is carried out by utilizing the interaction of metal oxides with boroncarbide and carbon in vacuum. the obtained alloys is investigated and their crystal structure is determined. The hexaborides are distinguished by their low work

Card 1/2

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# CIA-RDP86-00513R001447020001-2

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Alloys of rare metals...

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function and slow evaporation which shows the prospect of using them as thermionic emitters. Their disadvantage is the small electhem as thermionic emitters. Their disadvantage is the small elec-trical resistance which makes their heating difficult. This proper-ty can be considerably improved by dissolving ceriumboride in them which leads to a solid solution of high electric resistance preserving the thermoelectric properties of the original borides. [Ab-stracter's note: Complete translation]

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18.600	- m-shnical
AUTHOR :	Samsonov, G. V. (Professor, Doctor of Technico Sciences) Sintering of Tungsten-Titanium-Cobalt Hard Alloy
TITIE:	Sintering of Tungsten
PERIODICAL:	Metallovedeniye i termication 1960, Nr 1, pp 25-27 (USSR) The influence of temperature and the duration of The influence of temperature of cobalt volatilization intering on the degree of cobalt volatilization intering on the degree of free carbon on sintering
ABSTRACT:	sincer is the effect itanium carbine following
	were investigated. were investigated. chemical composition were used: Mree; 0.41% 0. chemical composition were used: Mree; 0.41% 0. chemical composition were used: Mree; 0.41% 0.
1/EC	0.28% 0; 0.0375% at 1,5500 C 101 1; 10 and 100 vacuum furnace at 1,5500 of 0.1; 1; 10 and 100 120 min under pressures of 0.1; 10 and 100 120 min under pressures o
Card 1/54	





CIA-RDP86-00513R001447020001-2

77160 sov/129-60-1-8/22 Sintering of Tungsten-Titanium-Cobalt Hard The following conclusions were drawn: For Alloy in Vacuum preventing volatilization of cobalt during sinterpreventing volatilization of copait during sinter-ing carbide T15K in vacuum, the pressure in the furnace must not be below 10 mm Hg. With this pressure and a temperature of 1,4000 C the structure formation of the carbide is completed with in 12 hours. The carbide has high physical and mechanical properties and no porosity. In the atmosphere of hydrogen and at 1,5500 C, sintering lasts 3 to 4 hr. The addition of carbon to the initial material improves microstructure and physical and mechanical properties. However, as seen from Table 2, large additions of carbon impair the properties and prolong the sintering process. Card 3/

APPROVED FOR RELEASE: 08/22/2000

"APPROVED FOR RELEASE: 08/22/2000 CIA-RDP86-00513R001447020001-2 77160 Sintering of Tungsten-Titanium-Cobalt Hard Alloy in Vacuum sov/129-60-1-8/22 Relationship between the properties of carbide sintered in vacuum and the free carbon content in the mixture. Hardness Southe Cfree content 070 Rc Gravity -----هايجور بارجلسين <u>....</u> 11,20 11,31 11,43 11,23 11,05 10,54 91,2 90.9 90.7 90 0,05  $0.1 \\ 0.2$ 0,5 ç0 39,7 1 i,5 There are 2 tables; and 2 figures. Institute of Metalloceramics and special alloys AS UKRSSR ASSOCIATION: Card 4/4 4

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5 A·MSON 18.6000		77162 SOV/129-60-1-10/2	2
AUTHOR S:	Babich, B. N. (Engineer) (Candidate of Technical (Professor, Doctor of Te	conticat Doe	
TITIE:	Pressing and Sintering	cheskaya obrabotka metallov	<b>7</b> ,
PERIODICAL:	Metallovedeniye 1 termi 1960, Nr 1, pp 31-35 (U	SSR)	ing
ABSTRACT:	The first investigation powders of various comp earlier work (Samsonov SSSR, Vol 104, 1955). veloped a theory of si In this work the autho and sintering of (1) the evders, and (2) titan	of the plast carried out 1 ositions was carried out 1 ositions was carried out 1 description of the second Later on G. A. Meerson de- Later on G. A. Meerson de- ntering for plastic metals. Intering for plastic metals rs investigate the pressing the pre	g e loys The d
Card 1/7	powders, molar concer	film and TiB; $CrB_{2} = 4:17$ . Atration TiB; $CrB_{2} = 4:17$ . boride powders were prepare method, and double titaniu mogenization of these borid	<b>m−</b>

## CIA-RDP86-00513R001447020001-2

sov/129-60-1-10/22 77162 Pressing and Sintering of Boride Powders mixtures at 1,700° C for 1 hr in a vacuum. The size of particles of all three powders ranged between 2 and 3 micron. The weight of 1 ml of powders TiB2, CrB2, (Ti,Cr)B<sub>2</sub> is (in grams) 0.80, 1.05, 0.97, respectively. The method of investigating the process of pressing consists in studying the effect of holding under pressure on density of compressed briquettes, measuring the elastic aftereffect, and studying the effect on density of intermediate grating of compressed briquettes. None of the tested plasticizers markedly improved the pressibility of briquettes, although briquette strength was at a maximum when using F2Cl<sub>3</sub> solution. Fig. 1 shows the results of pressing depending on compacting pressure. The data show that TiB2 is endowed with the best pressibility. Card 2/7

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# CIA-RDP86-00513R001447020001-2

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Pressing and Sintering of Boride Powders

of the investigated materials is of major importance since the character of the relationship of aftereffect and pressure is connected with high brittleness and nonplasticity of borides. Sintering: In order to observe sintering conditions, the briquettes were compacted under a pressure of 3 ton/cm<sup>2</sup> and sintered in a vacuum (0.1 mm Hg) in a retort furnace with a graphite heater. To determine the optimum sintering tempera-ture the specimens were sintered within the 1,700-2,400° C range for 1 hr. It was found that the sintering process occurs in two stages: (1) minor density increase at maximum temperatures up to 2,100-2,200°C; and (2) intensive density increase above these tempera- $TiB_2$  boride and solid solution  $(Ti, Cr)B_2$  were held at 2,300° C while  $CrB_{,}$  was held at 2,000° C: The maximum density was obtained at a holding time of 120 min. As a result, the process of compacting boride briquettes in sintering consists in drawing particles into the pore space at temperatures of the second stage of sintering at which the forces of surface tension

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Pressing and Sintering of Boride Powders

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predominate over the strength of the particles which became plastic. The investigation shows the possibility of pressing and sintering separately, instead of using the complex and expensive method of hot pressing. There are 3 figures; 3 tables; and 12 references, 10 Soviet, 1 U.S., 1 German. The U.S. reference is: Chiotti, P., "J. Amer. Cer. Soc.", Vol 35, 1952.

Card 7/7

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## CIA-RDP86-00513R001447020001-2

\$/131/60/000/01/011/017 B015/B001 Samsonov, G. V., Yasinskaya, G.A., 15(2) AUTHORS : Tay Shou-vey Crucibles of Difficultly Fusible Carbides, Borides, and TITLE: Nitrides Ogneupory, 1960, Nr 1, pp 35 - 38 (USSR) In this paper, the authors mention the results of the ex-PERIODICAL: perimental use of the above crucibles for the melting of metals. Figure 1 shows the scheme of the mold for hot-pressing ABSTRACT: the crucibles, and figure 2 the finished crucibles. The experimental results are shown in the table. Crucibles of TiC, TiN, TiB<sub>2</sub>, TiB<sub>2</sub> + 5% Mo, and CrB<sub>2</sub> were investigated. The interaction between the crucible materials and the molten metals and slags, respectively, can be seen on microphotographs (Figs 3 and 4). The experiments showed that all crucibles are sufficiently stable to the effect of molten tin, bismuth, cadmium, and lead. Crucibles of chromic boride and of the alloy of  $TiB_2$  with molybdenum are stable to the effect of molten carbon steel and cast iron. Crucibles of Card 1/2

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stem Crb2-M	tant at a value of 1,020 _ 9_0 testics at 17 molecular % of $CH_2$ o is eutectical, with two eutectics at 17 molecular % of $CH_2$ of 94 molecular % of $CH_2$ (~2,120°C), and little mutual solubility of s in a solid state. There are 2 figures and 4 references: 3 Soviet is in a solid state.	۸. ja
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	S/180/60/000/02/017/028 E111/E152
AUTHORS: TITLE:	Ell1/El52 Koval chenko, M.S., Samsonov, G.V., and Yasinskaya, G.A. (Kiyev) Alloys of Transition-Element Borides with Other Metals L: Izvestiya Akademii nauk SSSR, Otdeleniye tekhnicheskikh nauk, Metallurgiya i toplivo, 1960, Nr 2, pp 115-119 (USSR) nauk, Metallurgiya i toplivo, 1960, Nr 2, pp 115-119 (USSR)
ABSTRACT:	The high brittleness of transition-metal borides limited the application (Ref.3) of some of their useful properties (Refs 1, 2). The authors suggest that it is therefore important to study their pseudo-binary alloys therefore important to study their pseudo-binary alloys therefore important to study their pseudo-binary alloys therefore important to study their pseudo-binary alloys
	showed that for phases, which might be use. Ternary boride phases, which might be advantageous (Ref 5), have not been studied much advantageous (Ref 5), have not been studied much (Refs 6-8). In the present work the reaction of borides (Refs 6-8). In the present work the reaction of borides with metals in the pseudo-binary systems was: with metals in the pseudo-binary systems was: with metals in the pseudo-binary systems was: arBorMood TiBorMo, CrB2-Mo, TiB2-Cr and ZrB2-Cr.
Card 1/2	$3 \frac{1}{2rB_2-M_0} \frac{T_{1B_2}M_0}{T_{1B_2}M_0}$ , $\frac{3}{2rB_2-M_0}$ , $\frac{1}{T_{1B_2}M_0}$ , $\frac{3}{2rB_2-M_0}$ , $\frac{1}{T_{1B_2}M_0}$ , $\frac{3}{2rB_2-M_0}$ , $\frac{1}{T_{1B_2}M_0}$ , $\frac{1}{T$

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Alloys	S/180/60/000/02/017/028 <b>B</b> 111/ <b>B</b> 152 f Transition-Element Borides with Other Metals In addition micro- and macro-hardness determinations of phases were made together with metallographic ari X-ray examinations. The hypotectic diagrams for the above systems are given in Figs 1, 2, 3, 4 and 5 respectively. <u>Tay Shou-bey</u> of the Institut Metallov AN KNR ( <u>Institute</u> <u>Tay Shou-bey</u> of the Institut Metallov AN KNR ( <u>Institute</u> of Metals Academy of Sciences CPR), G.N. Makarenko and V.I. Kostikov participated in the experimental work.	
Card 2/2	V.I. Kostikov participated in the experimental of the experimental of the second secon	



## CIA-RDP86-00513R001447020001-2

• • • • • 28311 s/081/61/000/016/018/040 B143/B101 5-2410 Samsonov, G. V., Paderno, Yu. B., Fomenko, V. S. Production and some properties of neodymium hexaboride AUTHORS : Referativnyy zhurnal - Khimiya, no. 16, 1961, 87, abstract 1685 (Sb. "Vopr. poroshk. metallurgii i prochnosti materialov"; TITLE: PERIODICAL: Kiyev, AN USSR, no.-8, 1960, 66 - 68) TEXT: Two methods of NdB<sub>6</sub> production by means of the reactions  $Nd_2O_3 + 3B_4C \longrightarrow 2NdB_6 + 3CO and Nd_2O_3 + 15B \longrightarrow 2NdB_6 + 3BO were described.$ In both cases the process took place in a vacuum furnace with graphite heater in the temperature interval 1100 - 1800°C, with permanent removal of the gaseous reaction products. The completeness of the reaction was checked by X-ray pictures and analytically as well as according to the yield. In both cases the holding time for the optimum production process of NdB<sub>6</sub> at 1600 - 1650°C is one hour. NdB<sub>6</sub> is a finely disperse dark blue powder, the parameter of the crystal lattice is a = 4.124 Compact NdB<sub>6</sub> Card 1/2

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### CIA-RDP86-00513R001447020001-2

28311 s/081/61/000/016/018/040 B143/B101

Production and some... is obtained from powder by the method of hot pressing. The optimum holding time was 15 - 20 min at 2000°C at a pressure of  $175 - 200 \text{ kg/cm}^2$ . In this case minimum porosity of the compact NdB<sub>6</sub> was 3%. The resistivity of NdB<sub>6</sub> is 28 µohm.cm. Studies of the thermoelectromotive force of NdB<sub>6</sub> paired as thermocouple with Pt in the interval 20 -  $700^{\circ}$ C gave a negative value of a thermocouple with Pt in the interval 20 -  $700^{\circ}$ C gave a negative value of the coefficient of thermoelectromotive force whose absolute amount the coefficient of thermoelectromotive force whose absolute amount of NdB<sub>6</sub> is 0.7 (at 1600°C). The microhardness of NdB<sub>6</sub> at an indentor load of 70 g was 2540 ± 170 kg/mm<sup>2</sup>, the melting temperature of NdB<sub>6</sub> was 2540°C. The work function of the electrons in thermionic emission is 3.97 ev.

Card 2/2

APPROVED FOR RELEASE: 08/22/2000

s/058/61/000/007/054/086 A001/A101

15.2660 AUTHORS:

TITLE:

Samsonov, G.V., Neshpor, V.S. On the problem of magnetic properties of metal-like compounds Referativnyy zhurnal. Fizika, no. 7, 1961, 282, abstract 7E472 (V

PERIODICAL:

sb. "Vopr. poroshk. metallurgii i prochnosti materialov", no. 8, Kiyey, AN UkrSSR, 1960, 90 - 98) The results of investigating magnetic properties of compounds of transition elements with C, N, B and Si make it possible to judge on the nature

of interatomic bonds in these compounds. The data known in literature on moleof interaction to control in where compounds. The dash known in fractions on molecular susceptibility  $\mathcal{X}_{m}$  and magnetic moment  $\mu_{\text{ef}}$  of metallic ions are presented. The  $\mathcal{X}_{m}$  and  $\mu_{\text{ef}}$  values of the studied compounds, reduced in comparison with the TEXT: values of the pure metals, indicate the formation in these compounds of a collecvalues of one pure mourie, include one formetrich in the crystal. The reduc-tive of electrons filling the overlapped dsp- band in the crystal. tive of electrons filling the overlapped usp- band in the crystal. The reduction degree of  $\mathcal{X}_m$  is related to the ionization potential magnitude of the metalloid. In the case of hexaborides of rare earths there is no decrease of  $\mathcal{X}_m$ ,

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	agnetic properties . e 4f-shell is screen co temperature depen	AO	756 058/61/000/007/0 01/A101 5d_electrons. maborides of rar	The
since the incomplete lata are presented as well as on the c nitrides.	e 4f-shell is screen on temperature depen concentration depende	ence of Acm 101 Some	e carbides, bori: . Boyarskiy	iez and
[Abstracter's note	: Complete translat	107.]	<b>X</b>	
Card 2/2				

A PARTY

SALSOLOV, G.V. Electronic structure and properties of nitrices of high-relting notals. Zhur. strukt. khin. 1 no. 4:147-452 N-D '60. 1. Institut motalloberaniki i spotsial'nykh spievev Al USS., Kiyov. (litricos)

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CIA-RDP86-00513R001447020001-2



APPROVED FOR RELEASE: 08/22/2000

82988 s/181/60/002/008/007/045

B006/B070

The Diffusion of Boron in Carbon

onto whose surface a 2 mm thick layer of a paste of amorphous boron was applied. After the samples had been dried at 150°C, they were enclosed in a graphite shell and preheated in an atmosphere of hydrogen (700 - 800°C, 60 - 80 min). After this treatment the samples were subjected to metallographic, chemical, and X-ray analyses. Further, the reverse process of diffusion of carbon in boron was investigated. For this purpose, boron samples of a porosity of 36% were employed. They were prepared by compression of boron powder and sintering at 1900°C. In this prepared by compression of boron powder and singering at 1,000 o. In this case there resulted a saturation of the carbon samples with carbon in 30 minutes in a vacuum oven at 1940°C. Experiments showed that in similar conditions the boron penetrates deeper in carbon (1.4 - 1.6 mm) than carbon does in boron (0.6 - 0.8 mm). This indicates a remarkably higher mobility of boron atoms. The diffusion coefficients were calculated to be  $6.2 \cdot 10^{-6} \text{cm}^2/\text{sec}$  (B-C) and  $1.8 \cdot 10^{-6} \text{cm}^2/\text{sec}$  (C-B). Numerical data for two samples showing boron content at different depths of the carbon sample (chemical analysis) are given in Table 1. Their graphical representation is given in Fig. 2. The boron concentration diminishes exponentially with depth. That a solid solution is formed due to

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	82988 of Boron in Carbon S/181/60/002/008/007/045 B006/B070
diffusion, is of graphite la (Fig. 3). Furt graphite is in bold Numerica	shown by an X-ray analysis. Here the interplanar spacings ttice are measured as function of boron concentration her, the temperature dependence of diffusion of boron in vestigated (Fig. 4). $D = 3.02 \exp(-28625/T)$ is found to 1 values are given in Table 2. There are 4 figures, 2 Soviet references.
ASSOCIATION:	Institut metallokeramiki i spetsial'nykh splavov AN USSR ( <u>Institute of Powder Metallurgy and Special Alloys of the</u>
•	<u>AS UkrSSR)</u>
SUBMITTED:	<u>AS UKRSSK)</u> October 20, 1959
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APPROVED FOR RELEASE: 08/22/2000

84084 s/181/60/002/009/025/036 Investigation of the Electrical Conductivity B004/B056 of Silicides of the Transition Metals the number of d-electrons in the free metal. The majority of the silicates investigated were metallic conductors with the exception of the disilicides of Ba, Cr, Fe, Re, and Mn, which are semiconductors. In Me - Si systems, in which the highest silicide (MeSi2) has metal conductivity, the electric resistance of the intermediate silicides decreases with increasing Si content. If, however, the highest silicide is a semiconductor, the reverse behavior is observed. The electric resistance of the disilicides of groups IV - VI is a function of the acceptor property fof the d-shell of the metal atom. The highest electric resistance was measured at VSi<sub>2</sub> ( $\xi_V = 0.111$ ). With  $f_{Me} > \xi_V$  the resistance of the disilicides decreases with increasing  $\mathbf{\tilde{F}}_{Me}$  just as in the case of carbides, nitrides, and borides of the transition metals. With  $Me \langle v'$ , the behavior is reversed like in the case of pure metals. The resistance of the disilicides of rare earths (fd-transition metals) is considerably higher than that of the disilicides of d-transition metals. L. Yudina, student at Livovskiy gosudarstvennyy universitet im. I. Franko (Livov State University imeni I. Franko) took part in the experiments. There are Card 2/3

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<pre>4 figures, 1 table, and 24 references: 17 Soviet, 1 US, 2 British, 1 German, and 1 Australian. ASSOCIATION: Institut metallokeramiki i spetsial'nykh splavov AN USSR, Kiyev (Institute of Powder Metallurgy and Special Alloys of the AS UkrSSR, Kiyev) SUBMITTED: November 9, 1959</pre>	of Silicides	n of the Electrical Conductivity S/181/60/002/009/025/036 of the Transition Metals B004/B056
Kiyev (Institute of Powder Metallurgy and Special Alloys of the AS UkrSSR, Kiyev)	4 figures, 1 1 German, and	d 1 Australian.
SUBMITTED: November 9, 1959	ASSOCIATION:	Kiyev (Institute of Powder Metallurgy and Special Alloys
	SUBMITTED:	November 9, 1959

9.4300 (1139,1160 onty) 24.7700 1043,1155,1158 S/063/60/005/004/021 A051/A029 NUTHOR: Samsonov, G.Y., Professor FITLE: New High-Temperature Semiconductors and Their Application FITLE: New High-Temperature Semiconductors and Their Application FITLE: Zhurnal Vsesoyuznogo Khimicheskogo Obshchestva im. D.I. Mende- leyeva, 1960, No. 5, Vol. 5, pp. 515-521 TEXT: With the development of high-temperature processes in chemistry, me- tallurgy, power engineering, etc., the need for semiconductor materials and aggressive media or mechanical stress has arisen. Modern techniques and aggressive media or mechanical stress has arisen. Modern techniques and aggressive media or mechanical stress has arisen. Modern techniques ind of cheap natural gas, operation of reactors and in burning of ordinary ficiency factor for the direct transformation of heat liberated in the burn- ficiency factor for the direct transformation of neatorials with a high ef- melting point of 2,000-2,500°C are required. This is accomplished by using melting point of 2,000-2,500°C are required. This is accomplished by using the metals of the transition group of the periodic table of elements to-		20615
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20615 s/063/60/005/005/004/021 A051/A029 New High-Temperature Semiconductors and Their Application gether with non-metals: boron, carbon, nitrogen, silicon, or by direct combination of the non-metals. The chemical stability and the electrical and magnetic properties of these compounds are determined by the participation of the electrons of the incompletely built d-shell of the transition metal in the chemical bond in addition to the valency electrons. The unique crystal structure of these compounds brings about the high melting point, hardness and heat-resistance. All these compounds are characterized by heterodesmic properties. The polarizing or accepting tendency of the transition metal atom, indicating the extent of the effect of the unfilled d-electron level on the distribution of the electron concentration in the crystal, is expressed by the relationship 1/Nn, where N is the quantum number of the d level, and n the number of electrons. Table 1 lists the electrophysical properties of silicides of transition metals, where the 1/Nn criterion varies according to the transition metal. An increase in this criterion, generally, would cause a shift of the relative maximum of the electron density toward the shells of the transition metal atoms, and this shift would be Card 2/17

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的目的的。我们是我们的问题,我们是我们的问题,我们是我们的问题。 20615 s/063/60/005/005/004/021 A051/A029 New High-Temperature Semiconductors and Their Application the much greater, the less the ionization potentials of the valency electrons of the non-metal atoms. In cases where conditions are created for a sharply defined asymmetry of the electron density distribution, energy breaks in the crystals take place, and zones of forbidden states of lesser or greater width occur, and these circumstances can cause semiconductor properties. A change in the electronic density causes an increase of the ion bond fraction expressed through the general shift of the electron collective toward the direction of the non-metal atom shells, and the formation of energy breaks sufficient for the occurrence of semiconductor properties. With a decrease in the ionization potential of the metalloid (when changing) to carbon), the valency electrons of the latter lend themselves more readily to bonding and the position of the relative maximum of the electron concentration shifts towards the metal atom, increasing with an increase in the value of 1/Nn. It is pointed out that the addition of metal atoms and nonmetals takes place by collectivized electrons, the zones of the s-,d-, and p-electron energy states overlap, and so semiconductor properties cannot be Card 3/17

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# New High-Temperature Semiconductors and Their Application

expected in most carbides. Experiments have proven this difficulty (Ref. 8-10). When shifting to the borides, the unity of the electron collective is maintained. The author further describes the borides as being compounds with a primarily metal nature of its bond and a metal type of conductivity (Ref. 8-10). Fig.1 is a diagram of the structural elements of silicon atoms (Ref. 8-10). Fig.1 is a diagram of the structural elements of silicon atoms (attributed lattices. Regarding the latter, semiconducting properties were in silicide lattices. Regarding the latter, semiconductor properties of the silicid-11,12). The author claims that the semiconductor properties of the silicides have the highest practical significance at the present time. All silies have the highest practical significance at the present time. All silithe electric resistance and the atomic content of silicon (Fig.2): 1) silithe electric resistance and the atomic content of silicon (Fig.2): 1) silicides forming Ti, Zr, V, Ta, W and Mo compounds, 2) those forming Cr, Fe, cides forming Ti, Zr, V, Ta, W and Mo compounds, 2) those forming Cr, Fe, silicide phases in the systems Me-Si follows a certain rule: with an insilicide phases in the systems Me-Si follows a certain rule: with an insilicide is a semiconductor, and decreases where the higher silicide has a

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New High-Temperature Semiconductors and Their Application metal conductivity. The reason for this rule is the fact that in systems with metal compounds the atoms of the metalloids, although forming covalent bonds with one another, their bond with the metals has a metallic nature and is achieved by the electron collective. A drop in the electric resistance of the silicides with an increase in temperature is explained mainly by the expansion of the elementary nucleus causing a lesser coverage of the zones (Ref. 7). In order to find and produce semiconductors with predetermined properties, it is important that the nature of the conductivity of the silicides, as well as other compounds of the same type be determined not by the interaction between the metal atoms, suggested in certain articles (Ref. 15), but mostly by the nature of the bond between atoms of the metal and non-metal, which determines the degree of filling of the energy bands in the crystal of the compound. In discussing the second large group of difficultly fusible compounds (non-metal compounds of silicon and boron with carbon and nitrogen, boron and silicon, and their respective alloys) it is noted that this group is represented exclusively by semiconductor phases, which have

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New High-Temperature Semiconductors and Their Application

already found practical application. Carbon and boron, and also the compounds of boron and silicon combined with phosphorus, and of aluminum with boron, belong to this group. The main characteristic of these compounds is the formation of covalent bonds between atoms in the composition of their non-metals. This leads to the formation of linear, chain, laminated or skeleton elements of non-metallic atoms from one or several kinds in their crystal structures. The special features of the semiconductor properties of the non-metal compounds are determined by the ability of the non-metal atom to give off the external electrons for bonding, which in the first approximation is evaluated by the magnitude of the ionization potential of the nonmetal atom. The same was noted for pure crystals from non-metals (Table 3). From here it is seen that the break between the permitted energy levels increases with an increase in the ionization potential of the non-metal atom, i.e., with an increase of the ion component of the bond. In non-metal difficultly fusible compounds the width of the forbidden zone increases with an increase of the ionization potentials of the components. Silicon carbide,

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New High-Temperature Semiconductors and Their Application SiC, is further discussed as being the most investigated compound of this type, and the formation of the n-conductivity in it is described. Fig.3 shows a typical curve of the relationship between the electroresistance of the SiC admixture and the temperature (Ref. 16). At the present time it has definitely been established that two chemical compounds exist in the system using the product of the second seco conductor properties, whereby the greatest thermal emf are noted in defective structures based on compounds of  $B_{12}C_2$  and  $B_{13}C_2$ . The specific electric resistance of the latter is of the order of 1 and 210 ohm cm; its relationship to temperature was studied only for  $B_{c}$  up to 2,100°C, and it was es-tablished that this carbide has a width of the forbidden zone equalling 1.64 ev and changes to self-conductivity at 1,400-1,450°C. A future commercial use is expected for silicon nitride as a high-temperature material. Boron nitride, known in two modifications: similar to the structure of graphite

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New High-Temperature Semiconductors and Their Application

(Fig. 4) and to cubic diamond-like structure, is also considered as a hightemperature semiconductor. The properties of only the ordinary graphitelike boron nitride have been studied until now. The alloys of boron and silicon (Ref. 24) have also semiconductor properties and have the outstanding feature of possessing a high heat-reasistance and chemical stability in acid and alkaline media. The semiconductor properties of boron have been more carefully studied in recent times. (Ref. 25). A study of the Hall effect, the thermal emf and rectifying properties of the boron single crystals has the thermal emf and rectifying properties of current rectification and phoshown that at high temperatures the crystals are hole conductors, and at low shown the temperature boron reveals effects of current rectification and pho-At room temperature boron reveals effects of current rectification and photoconductivity. Scientific interest is expressed in the electrical properties of boron phosphide, BP, belonging to the class of semiconductor comties of boron phosphide, BP, belonging to the class of semiconductor comties of the A H by type, and also in certain phosphides and sulfides of pounds of the A H by type, and also in certain phosphides and sulfides of the d- and f-transition metals. Variation in the electrical stability and the d- and f-transition metals. Variation in the alloys of metal-like com-

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New High-Temperature Semiconductors and Their Application

pounds not having semiconducting properties, together with semiconductor silicides or with non-metal semiconductors, and also alloys of non-metal difficultly fusible compounds. The alloy of boron carbide with molybdenum silicide is discussed as belonging to the class of Novotny phases with a wide range of homogeneity. These types of semiconductor phases are used for junctions in thermocouples intended for the direct measuring of temperatures of chemically-aggressive substances, molten metals, slag, and gases heated to very high temperatures (Fig.6). In the thermocouples TTT-1(PT-1), TTT-2 (PT-2), TT-3(PT-3), TT-4(PT-4) manufactured today, the external cover is made of molybdenum silicide, zirconium boride, titanium carbide and titanium boride, respectively. The internal rod is made of borinated graphite, which is found to be technically more convenient than using rods made of boron carbide. Thermocouples made of molybdenum and rhenium silicide, of which the first has metallic conductivity and the second is a semiconductor, are considered to have great prospects for the future. Further interest is revealed in silicon and boron nitrides as high-temperature thermistors and as

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New High-Temperature Semiconductors and Their Application

part of so-called non-wire or volume resistors (Fig. 8). Wave-guide absorbers are made of silicon carbide. The range of the positive coefficient of the electric-resistance of the silicon carbide admixture (600-1,500°C) is used in the operation of high-temperature carborundum heaters for electric resistance furnaces. High-temperature semiconductors based on silicon carbide are also used extensively as sources of infra-red radiation in spectroscopy and drying. The semiconductor properties of boron carbide are applied in automation, electrical engineering, for producing resistors compensating for the effect of temperature change of the surrounding medium on the showings of magnetic-electrical systems in electric-measuring devices (Ref. 29). Compounds of silicon and boron carbide are considered useful materials for producing high-ohm volume resistors (Ref. 33). By developing a production method of silicon carbide and of boron carbide single crystals of high purity, the latter could be used in industry as first-class rectifiers. There are 3 tables, 3 diagrams, 1 photograph, 4 figures and 33 references: 25 Soviet, 8 English.

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SAMSONOV, G.V.

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S/078/60/005/008/012/018 B004/B052

AUTHORS:Vereykina, L. L., Samsonev, G. V.TITLE:A Simple Method of Producing Titanium PhosphidesPERIODICAL:Zhurnal neorganicheskoy khimii, 1960, Vol. 5, No. 8,pp. 1888-1889

TEXT: The authors give a brief description of western papers on titanium phosphides (Refs. 1 - 6). They investigated the reaction of titanium powder and PH<sub>3</sub> in an apparatus depicted in a Fig. PH<sub>3</sub> was produced by igniting a stoichiometric mixture of aluminum powder and red phosphorus in a steel cylinder by means of a magnesium band. The aluminum phosphide was decomposed by intensive cooling with a 10% H<sub>2</sub>SO<sub>4</sub> solution in argon free from oxygen, and the mixture of argon and PH<sub>3</sub> was conducted over a quartz boat containing the titanium powder. The analysis of titanium phosphide was conducted according to a method by of HNO<sub>3</sub> and HF, the titanium was combined by a tartaric acid complex,

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Phosphides	of Producing Titanium	S/078/60/005/008/012/018 B004/B052
are listed in a in at 700°C. Ti	rus was precipitated as phos Table. The development of t 2 <sup>P</sup> develops at 800 <sup>o</sup> C after 6 Ti <sub>3</sub> P, assumed by the author gations. There are 1 figure,	sphomolybdic acid. The results titanium phosphide only sets 5 h, and TiP at 850°C. The rs, must yet be proved by , 1 table, and 6 non-Soviet
ASSOCIATION:	(T-a+i+uto of Cormets and i	spetsial'nykh splavov toriya tugoplavkikh materialov <u>Special Alloys of the Academy</u> atory for <del>High melting</del> Regractory
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SAM	SONOV, G.V.	s/078/60/005/008/017/0	18
		ВОО4/ВО52	
AUTHORS:	Paderno, Yu. B., Samson	10v, G. V.	
TITLE:	Borides of the Metals of		
PERIODICAL:	Zhurnal neorganicheskov pp. 1914-1915	y khimii, 1960, Vol. 5, No. 8,	
of Hexaborides neorganichesko that he used b equations are experimental t point of the f chemical analy radiographic at the chemical a	of Rare Earths and Yttri y khimii", 1959, Vol. 4, oron carbide containing 7 only applicable for B <sub>4</sub> C we emperatures described, and ormation kinetics of bori ses confirm the development halysis proves the existent halyses are dubious; (4)	y N. N. Tvorogov on "Investigation ium" published in the "Zhurnal pp. 1961-1966: (1) Tvorogov state 72.61% of B, while his reaction with 78.3% of B; (2) the re unintelligible from the view- ides; (3) the data of the ent of <u>hexaborides</u> ; <sup>1</sup> while the ence of several phases. Therefore, the lattice constants of termined densities are also doubte	
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 (5) The published data are incomplete. Finally, the authors report that they produced thulium tetraboride by reducing thulium oxide by means of boron at 1600 - 2100°C. The respective lattice constants are given. There are 13 references: 10 Soviet, 1 US, and 2 Czechoslovakian.

 ASSOCIATION:
 Institut metallokeramiki i spetsial'nykh splavor Akademii nauk USSR (Institute of Cermets and Special Alloys of the Academy of Sciences UkrSSR)

 SUBMITTED:
 November 13, 1959

APPROVED FOR RELEASE: 08/22/2000

名作法语:研究新游文学科教教会起来的影响和新教授。 高学校学校的和学校和教育的学校的学校。

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24, <b>1700</b> authors:	Portnov, K. I., Sansonov, G. V., Solonnikova, L. A.
TITLE :	Melts in the System Boron - Silicon - Carbon
PER IODI CAL:	Zhurnal neorganicheskoy khimii, 1960, Vol. 5, No. 9, pp. 2032-2041
determined by and the melti B C-Si and Si analyses (Tab which is clos the specific approximately 30 with denser pa between 2200 Si content of	nditions of synthesis and properties of some B-Si-C melts were microscopic-, X-ray-, microanalytical-, and chemical analyses, and temperature and electrical properties of the melts C-B were determined. On investigating B <sub>4</sub> C-Si melts, chemical te 1) showed that a silicon content is found in the mixture to the theoretical value of 25-35 wt% Si. When determining weight (Table 2) a maximum value was found to be attained at weight (Table 2) a maximum value was found to be attained at ching. At an Si content of 10-50% the melting point varies and 2400°C, to decrease at 70% Si to 1600°-1700°C. At an approximately 25 wt% in the alloy, a hardness maximum of about approximately 25 wt% in the alloy, a hardness maximum of about the sing thermo-electromotive force was determined, and the

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	ystem Boron - Silicon - Carbon 5/078/60/005/009/010/017 B015/B064
(Table 3) prov assumed to be alloys (Tables	semiconductor properties. $B_4^{C-Si}$ alloys with 25 - 50% Si ed to be most heat resistant. A ternary compound $B_5^{SiC_2}$ was present. Similar results were also obtained with SiC-B 4-6), and the formation of the ternary compound $B_3^{Si_2C_2}$
with the therm ing values of	150-electromotive force of the mana, <u>F. I. Shamray</u> , and 150-200 µb/degree. <u>A. A. Kalini</u> na, <u>F. I. Shamray</u> , and at al. are mentioned in the paper. There are 13 figures, 25 references: 17 Soviet, 1 German, 6 US, and 1 British.
ASSOCIATION:	Vsesoyuznyy institut aviatsionnykh materialov ( <u>All-Union</u> <u>Institute for Aviation Materials</u> ). Institut metallokeramiki i spetsial'nykh splavov Akademii nauk USSR ( <u>Institute of</u>
	i spetsial nykh splavov Akademii Hadd of the Academy of Powder Metallurgy and Special Alloys of the Academy of Sciences of the UkrSSR)
SUBMITTED:	June 4, 1959
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		S/051/60/008/03/026/038 E201/E191
•	AUTHORS:	Serebryakova, T.I., Paderno, Yu.B., and Samsonov, G.V.
	TITLE:	The Emissivities of Powders of Some Refractory Compounds
		L: Optika i spektroskopiya, 1960, Vol 8, Nr 3, pp 410-412 (USSR)
	ABSTRACT: Card 1/2	The authors report measurements of the emissivities of powders of <u>borides</u> , 'carbides' and <u>nitrides</u> of refractory and rare-earth metals. Measurements were carried out with an instrument shown in a figure on p 410. This instrument simulated closely an absolute black body. A tantalum cylinder 5 (20 mm diameter, 50 mm height) served as a heater. Inside the cylinder 5 there was another smaller tantalum cylinder 6 (8 mm diameter, 20 mm height) which was placed concentrically with the cylinder 5. In each of the cylinders there was a small aperture and these apertures were aligned horizontally. The lower ends of the two tantalum cylinders were fixed to a molybdenum plate 4 which was pressed against the cylinder 5 by a spring. The whole instrument was enclosed in a glass bulb 1. The inner cylinder 6 was coated with 100 µ thick layer of paste prepared from a fine powder (particles of

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## S/051/60/008/03/026/038 E201/E191

The Emissivities of Powders of Some Refractory Compounds

2-3  $\mu$  diameter) of the refractory material mixed with a binder. Temperature of the inner cylinder surface (the brightness temperature, T<sub>b</sub>) and temperature in the aligned apertures (the true temperature T<sub>t</sub>) were measured with an pyrometer OPPIR-09. Absorption in the glass bulb was found to be negligible. The emission intensities were measured at 650 mµ and the emissivities were calculated using the following formula:

$$\ell_{\rm n} \epsilon_{\lambda} = \frac{c}{\lambda} \left( \frac{1}{T_{\rm t}} - \frac{1}{T_{\rm b}} \right)$$

where c = 1.438 cm/deg and  $\lambda$  is the wavelength. The measured emissivities of pure tantalum at temperatures from 800 to 2000 °C agreed well with the published values (Table 1). The measured emissivities of ~LaB6, ~NdB6, ~SmB6,  $\Lambda GdB6$ ,  $\Lambda YB6$ , ZrB2,  $\Pi HfB2$ ,  $B_4C$ ,  $\Pi TiC$ ,  $\Lambda Cr7C3$  and BN powders at temperatures from 850 to 1650 °C are listed in Table 2. There are 1 figure, 2 tables and 6 references, of which 3 are Soviet, 2 English and 1 German.

SUEMITTED: August 8, 1959

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CIA-RDP86-00513R001447020001-2



APPROVED FOR RELEASE: 08/22/2000

85049 s/126/60/010/004/022/023 E073/E435 Electrical Properties of Lanthanum Boride  $\boldsymbol{\rho}_{o} = \boldsymbol{\rho}(1 - \mathbf{P})$  $\boldsymbol{\rho}_{o} = \boldsymbol{\rho} \exp\left(-\frac{\mathbf{A}}{1 - \mathbf{P}}\right)$ (4) (5) These dependences were obtained for the conductivity of a mixture In the case under consideration, the specimen can be considered as consisting of two phases, the compact material and It was found that the experimental results agree best with those obtained by Eq.(2) of Landau and Lifshits (Ref.2) cavities. although this equation was derived on the assumption that the difference between the conductivities of the phases was low. As was to be anticipated, the emf proved practically independent of the porosity (Fig.2). On a specimen with a 2% porosity the temperature dependence of the electric resistance of lanthanum hexaboride was measured up to 2000°C (Fig. 3). It was found that lanthanum boride is a typical metallic conductor with a thermal resistance coefficient of 0.060 microohm cm/°C. This value is considerably lower than the thermal resistance coefficient of Card 2/3

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Electrical	Properties	S/12 E073	850 6/60/010/0 /E435	49 04/022/023	
larger rigi that of the boride is a	dity of the crys metal (the chara 85°K whilst that he energy states	is attributed to tal lattice of h acteristic torrest	rature of 152°K) ar	compared t lanthanum	
	Institut metall AN USSR ( <u>Instit</u> AS UkrSSR)		- v ielere	nces: 4 So	viet X
SUBMITTED:	March 8, 1960, April 27, 1960,			<u></u>	
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83664 5/073/60/026/004/002/009 B016/B054 only 2308 15,2142 Paderno, Yu. B., Fomenko, V. S., and Samsonov, G. V. AUTHORS: Production and Some Properties of Neodymium Revelocide TITLE: Ukrainskiy khimicheskiy zhurnal, 1960, Vol. 26, No. 4, PERIODICAL: pp. 409-411 TEXT: The authors studied two methods of producing neodymium hexaboride: 1) the reduction of neodymium cride by the carbon of boron carbide with simultaneous reaction of the metal with boron, and 2) direct reduction of the metal oxide by boron (see reaction schemes). In both cases, the process was carried cut in a vacuum furnace with a graphite heating element (1100 ~ 1800°C). The gaseous reaction products were continuously .pumped off. The completeness of the reaction process was controlled by means of X-ray and chemical analyses of the product. The authors conclude from the results that in both cases the best results of hexaboride production are attained by heating the components to 1500-1550°C for 1 h. A finely disperse, dark-blue powder was formed, whose B-content was near the stoichiometric composition. The parameter a = 4.124 A was calculated Card 1/3

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Production and Some Properties of Neodymium Hexaboride	s/073/60/026/004/002/008 B016/B054
by the data of the radiograph (Table 1), * In publications (Ref. 2), Compact samples neodynium hexaboride by pressing at 2000°C	) for 15-20 min at a pressure
of 175-200 kg/cm <sup>2</sup> (optimum conditions). Mi was 3%. The value measured by the authors (20 µ chm - cm) lay considerably below that The coefficient of the electromotive force	ninum porosity of these samples for the electrical resistivity to the metal (64.3 µ ohm • cm). e, measured as a BN <sub>6</sub> -Pt thermo-
couple between room temperature and 700°C, temperature, as corresponds to metallic of measured the radiation coefficient at 1600 melting temperature, and the electron work properties of noodymium heraboride with the	, rises continuously with the onductivity. Finally, the authors O <sup>C</sup> C, the microhardness, the c function. A comparison of the hose of the borides of other rare with and the work function
increase in the order from lanthanum to m Hund's rule. There are 1 table and 12 ref	ANDVALIAN, ILLA SEASON PASSA
2 German.	
Card 2/3	